

APPARATUS AND METHOD FOR RAPID PHOTO-THERMAL SURFACE TREATMENT

ABSTRACT

An apparatus for surface treating a semiconductor wafer includes a surface treatment chamber and a source of radiation. The semiconductor wafer disposed inside the chamber is illuminated with radiation sufficient to create a plurality of electron-hole pairs near the surface of the wafer and to desorb ions and molecules adsorbed on the surface of the wafer.

426JIS6695/4.440738-1

TOP SECRET 426JIS6695/4.440738-1